	Hits	Search Text	DBs
47	0	or conductive or gate) same (resist or photoresist) same (patterns) or mask) same (etchs)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
48	U	strip\$6 same (resid\$4 or remain\$5) same (amino\$4ethanol	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
49	1 .	((resist or photoresist) same strip\$6 same (amino\$4ethanol near20 glycon near4 ether))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
50		((resist or photoresist) same strip\$6 same (amino\$4ethanol near20 glycol near4 ether))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
51	3	((resist or photoresist) same strip\$6) and (strip\$4 same (amino\$4 near4 ethanol near20 glycol near4 ether))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
52	1	or conductive or gate) same (resist or photoresist) same (pattern\$3 or mask) same (etch\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
53		((resist or photoresist) same strip\$6) and (strip\$4 same (amino\$4ethanol near20 glycol	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
54	25	((resist or photoresist) same strip\$6) and (strip\$4 same ((amino\$4ethanol near20 glycol near4 ether) or (Nagase near4 strip\$4)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB